

Title (en)

SYSTEMS AND METHODS FOR IMPLEMENTING AN INTERACTION BETWEEN A LASER SHAPED AS A LINE BEAM AND A FILM DEPOSITED ON A SUBSTRATE

Title (de)

SYSTEME UND VERFAHREN ZUR IMPLEMENTIERUNG EINES ZUSAMMENWIRKENS ZWISCHEN EINEN ALS LINIENSTRAHL GEFORMTEN LASER UND EINEN AUF EINEM TRÄGER NIEDERGESCHLAGENEN FILM

Title (fr)

SYSTEMES ET PROCEDES DE MISE EN OEUVRE D'UNE INTERACTION ENTRE UN LASER FORME EN UN FAISCEAU LINEAIRE ET UN FILM DEPOSE SUR UN SUBSTRAT

Publication

**EP 1887912 A4 20101110 (EN)**

Application

**EP 06760377 A 20060525**

Priority

- US 2006020223 W 20060525
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Abstract (en)

[origin: WO2006127891A2] A laser crystallization apparatus and method are disclosed for selectively melting a film such as amorphous silicon that is deposited on a substrate. The apparatus may comprise an optical system for producing stretched laser pulses for use in melting the film. In still another aspect of an embodiment of the present invention, a system and method are provided for stretching a laser pulse. In another aspect, a system is provided for maintaining a divergence of a pulsed laser beam (stretched or non-stretched) at a location along a beam path within a predetermined range. In another aspect, a system may be provided for maintaining the energy density at a film within a predetermined range during an interaction of the film with a shaped line beam.

IPC 8 full level

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CPC (source: EP)

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Citation (search report)

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